

This Page Is Inserted by IFW Operations
and is not a part of the Official Record

BEST AVAILABLE IMAGES

Defective images within this document are accurate representations of the original documents submitted by the applicant.

Defects in the images may include (but are not limited to):

- BLACK BORDERS
- TEXT CUT OFF AT TOP, BOTTOM OR SIDES
- FADED TEXT
- ILLEGIBLE TEXT
- SKEWED/SLANTED IMAGES
- COLORED PHOTOS
- BLACK OR VERY BLACK AND WHITE DARK PHOTOS
- GRAY SCALE DOCUMENTS

IMAGES ARE BEST AVAILABLE COPY.

**As rescanning documents *will not* correct images,
please do not report the images to the
Image Problem Mailbox.**

IN THE ABSTRACT

Please amend the ABSTRACT as follows:

--A method for forming an oxide layer ~~steam oxidation process~~ which provides uniform coverage of oxygen radicals across a surface of a substrate to enhance the oxidation rate and form a uniform layer of SiO₂. The method for forming an oxide layer ~~steam oxidation process~~ provides the heat and oxygen radicals for SiO₂ formation through the combustion of a process flame. The process flame can be fueled by a combination of H₂ and O₂ process gases. The process flame can include a plurality of process flames directed substantially perpendicular to the target substrate to provide uniform heating of the substrate and a uniform deposition of oxygen radicals across the surface of the substrate to enhance the formation of an oxidation layer.--